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Ti Sputtering Film using Sputter#3 (8-18-2016)

Condition: 3 mT, 100 W (312 V), Ar flow-rate=25 sccm, 25mm/9 (tilt angle), and Sputtering Time=600 seconds.

Result:

- 1) Film thickness measured by Ellipsometer (see next page)=13.4 nm.
- 2) Ti Sputtering Rate=1.34 nm/min.

Figure 1 Ti Film Thickness measured by Ellipsometer.

